Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	4	("5827410" "6454258").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 11:54
S2	403	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and workpiece adj3 (carrier holder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 12:26
S3	81	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and workpiece adj3 (carrier holder) and (workpiece substrate) with (flat)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:26
S4	0	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and workpiece adj3 (cage) and (workpiece substrate) with (flat)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:26
S5	0	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and protect\$4 adj3 (cage) and (workpiece substrate) with (flat)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:26
S6	0	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and protect\$4 near5 (cage) and (workpiece substrate) with (flat)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:24
S7	0	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and protect\$4 near5 (carrier) and (workpiece substrate) with (flat)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:28
S8	96	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and protect\$4 near5 (carrier)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:34

	1					
S9	81	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and protect\$4 near5 (carrier) and (tank vessel) with (fluid solution bath)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:41
S10	66	S9 not S8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR ·	ON	2007/04/11 13:37
S11	42	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and protect\$4 near5 (carrier) and (tank vessel) with (fluid solution bath) not \$9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 13:45
S12	153	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and workpiece near5 (carrier) and (tank vessel) with (fluid solution bath) not S9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 14:12
S13	. 165	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and workpiece near5 (holder) and (tank vessel) with (fluid solution bath) not S12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 14:43
S14	42	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (workpiece near5 (holder)) with hole and (tank vessel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 14:43
S15	71	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (workpiece near5 (holder)) with (aperture hole) and (tank vessel)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 14:48
S16	29	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (workpiece near5 (holder)) with (aperture hole) and (tank vessel) not \$14	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:19

S17	126	((Substrate workpiece) near5 (holder carrier)) with (aperture hole) and (tank vessel) and immers\$4 with (Substrate workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 15:03
S18	11	((Substrate workpiece) near5 (holder carrier)) with (perforat\$4) and (tank vessel) and immers\$4 with (Substrate workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 15:04
S19	18	("204"/297.01.ccls.) and (workpiece substrate) with (flat)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:27
S20	190	("204"/297.01.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:48
S21	9	("4059493" "4328076" "4569744" "4714535" "5620586" "5744013" "5766430" "5776327" "5938899").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/04/11 16:30
S22	. 0	("204"/259,297.01.ccls.) And (shutter orifice) with (diameter size) same vary\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:49
S23	1	("204"/259,297.01.ccls.) And (shutter orifice) with (diameter size)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:50
S24	14	("204"/259,297.01.ccls.) And (vary) with (diameter size)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:52

				ı		
S25	0	("204"/259,297.01.ccls.) And (vary) with (aperture)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:52
S26	2	("204"/259,297.01.ccls.) And (vary\$3) with (aperture)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:53
S27	2	("204"/259,297.01.ccls.) And (vary\$3) with (hole)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:53
S28	209	("204"/\$.ccls.) And (vary\$3) with (hole)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 16:54
S29	2	("204"/\$.ccls.) And basket same ((vary\$3) with (hole))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:00
S30	1	("204"/\$.ccls.) And basket same ((vary\$3) with (aperture))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:01
S31	8	("204"/\$.ccls.) And (tank container) same ((vary\$3) with (aperture))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:04
S32	29	("204"/\$.ccls.) And (tank container) same ((vary\$3) with (size)) same (hole aperture)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:11

S33	4	("205"/\$.ccls.) And (tank container) same ((vary\$3) with (size)) same (hole aperture) not S32	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/04/11 17:13
S34	1	("204"/\$.ccls. "205"/\$.ccls.) And (shutter) same ((vary\$3) with (size)) same (hole aperture) not S32	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:15
S36	8	("204"/\$.ccls. "205"/\$.ccls.) And (shutter) same ((vary\$3) with (size))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:18
S37	4	("204"/\$.ccls. "205"/\$.ccls.) And (displaceable near10 shutter)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:20
S38	86	("204"/\$.ccls. "205"/\$.ccls.) And (aperture near10 shutter)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:20
S39	0	("204"/\$.ccls. "205"/\$.ccls.) And (aperture near10 shutter) same basket	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:05
S40	1	("204"/\$.ccls. "205"/\$.ccls.) And (aperture near10 shutter) same tank	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:21
S41	40	("204"/\$.ccls. "205"/\$.ccls.) And (orifice near10 plate) same tank	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:31

S42	38	("204"/\$.ccls. "205"/\$.ccls.) And	US-PGPUB;	OR	ON	2007/04/11 17:45
	30	(orifice near10 plate) same adjust\$4	USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB			2007/0 1/11 17:13
S43	478	("204"/\$.ccls. "205"/\$.ccls.) And drain near5 (baffle gate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:46
S44	0	("204"/\$.ccls. "205"/\$.ccls.) And (drain near5 (baffle gate)) same basket	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:46
S45	3	("204"/\$.ccls. "205"/\$.ccls.) And (drain near5 (baffle gate)) same tank	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:48
S46	9	("204"/\$.ccls. "205"/\$.ccls.) And (drain near5 (baffle gate)) same (vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:49
S47	2	("204"/\$.ccls. "205"/\$.ccls.) And (drain near5 (baffle)) same (vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:50
548	323	("204"/\$.ccls. "205"/\$.ccls.) And electroplating And (drain) with (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 17:53
S49	0	("205"/96.ccls.) And (aperture with vary\$4) same basket	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:06

			•			
S50	6	("205"/96.ccls.) And (aperture with vary\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:08
S51	278	("205"/96.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:19
S52		("205"/96.ccls.) And (hole with vary\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:09
S53	3	("205"/96.ccls.) And (hole with diameter) same center	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:09
S54	9	("205"/96.ccls.) And size near5 distribution	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/11 18:19
S55	34	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (workpiece near5 (holder)) with (aperture hole) and (tank container vessel) and reservoir	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:21
S56	5573	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (tank container vessel) and reservoir	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:22
S57	1101	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (tank container vessel) and reservoir and pump and (fluid liquid solution) near5 level	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:23

S58	481	(Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (tank container vessel) and reservoir and pump and (fluid liquid solution) near5 level and immers\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:23
S59	251	("205"/\$.ccls. "204"/\$.ccls.) and (Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (tank container vessel) and reservoir and pump and (fluid liquid solution) near5 level and immers\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:35
S60	69	("205"/\$.ccls. "204"/\$.ccls.) and (Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (tank container vessel) and reservoir and pump and ((fluid liquid solution) near5 level) with control\$4 and immers\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:48
S61	25	("205"/\$.ccls. "204"/\$.ccls.) and (Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (barrel) and flat with (substrate work adj piece workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:51
S62	21	("205"/\$.ccls. "204"/\$.ccls.) and (Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (barrel) and flat near7(substrate work adj piece workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 11:55
S63	20	("205"/\$.ccls. "204"/\$.ccls.) and (Etching anodizing electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) same (barrel) and flexible near7 (substrate work adj piece workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 14:00
S65	1705	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and cathode with protect\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 14:01

			•	•		•
S66	6	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and cathode with protect\$4 adj3 screen	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 15:49
S67	2	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and drain near5 door	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:12
S68	4	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 door) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 15:53
S69	1	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 shutter) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 15:54
S70	15	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 baffle) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:09
S71	74	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 plate) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:09
S72	14	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 plate) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:18
S73	254	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 valve) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/04/12 16:22

S75	9	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and ((drain near5 valve) with automatic\$4) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:25
S76	12	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 actuat\$4) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR ·	ON	2007/04/12 16:34
S77	19	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 actuat\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:28
S78	1416	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:35
S79	0	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 chut) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:36
S80	7	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 gate) same (tank vessel container)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:37
S81	9	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (drain near5 gate) same (tank vessel container) not semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/04/12 16:37